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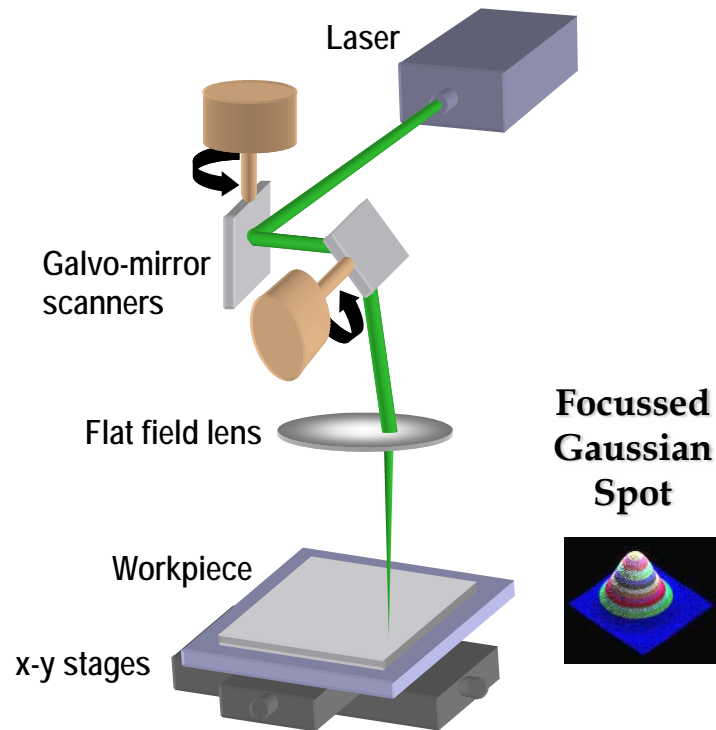
The Use of Lasers in Target Manufacture

Neil Sykes

Micronanics Limited



- Serial writing with focus spot
- Low M^2 (gaussian) laser beams
- High speeds - to 10m/sec
- Product designs CAD-CNC programming



Industrial applications

- MEMS prototyping
- Wafer cutting/ scribing/ drilling (Si, Sapphire, SiN)
- Circuit tuning, scribing and microvia drilling
- Probe card drilling
- Fuel injector drilling
- Solar panel and cell scribing
- Displays thin film scribing
- Aerosol atomizer drilling
- Gas sensor drilling
- Fibre stripping, cleaving & tip lensing



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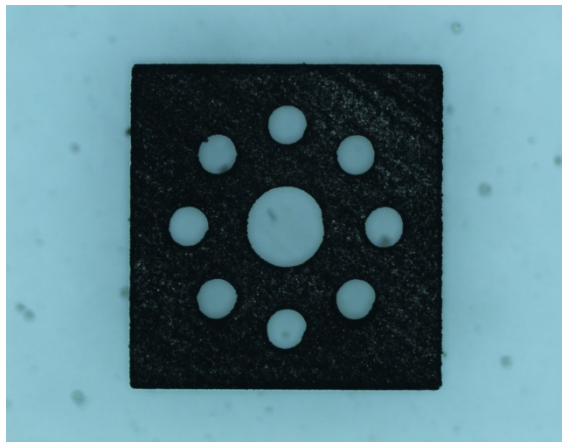
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- 355nm Coherent Avia
- Machines most materials in a serial scribing fashion.
- CAD files (DXF) can be imported to allow rapid machining of complex patterns.
- Rapid part prototyping.
- Galvo-scanner and/or stages

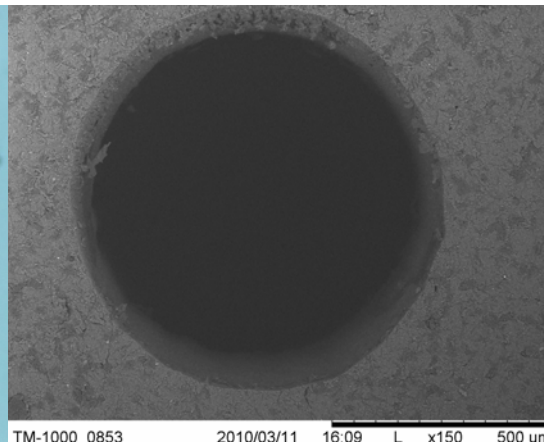




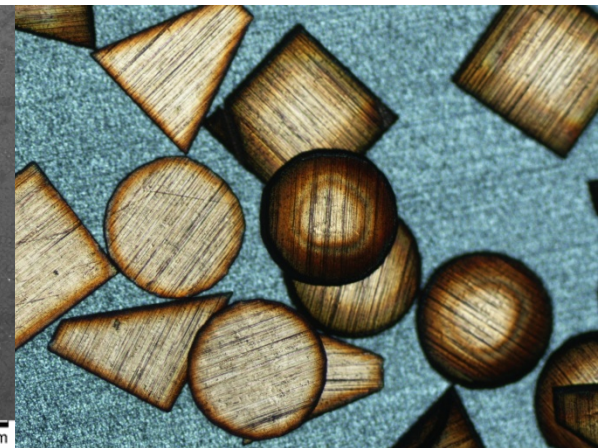
- Wide variety of materials can be processed
 - Metals (Stainless Steel, Copper, Brass, Aluminum)
 - Silicon, Ceramics, glass, polyimide
 - Almost any shape hole can be machined
 - Up to 500 μ m thick in most materials (>2mm in some)
 - High speed, little debris and small heat affected zone
 - Flexibility of CAD-CAM allows rapid prototyping and small batch manufacturing
 - Enables complex mask manufacture for Excimer systems



Pyrolytic Carbon



Kalrez® (Dupont)



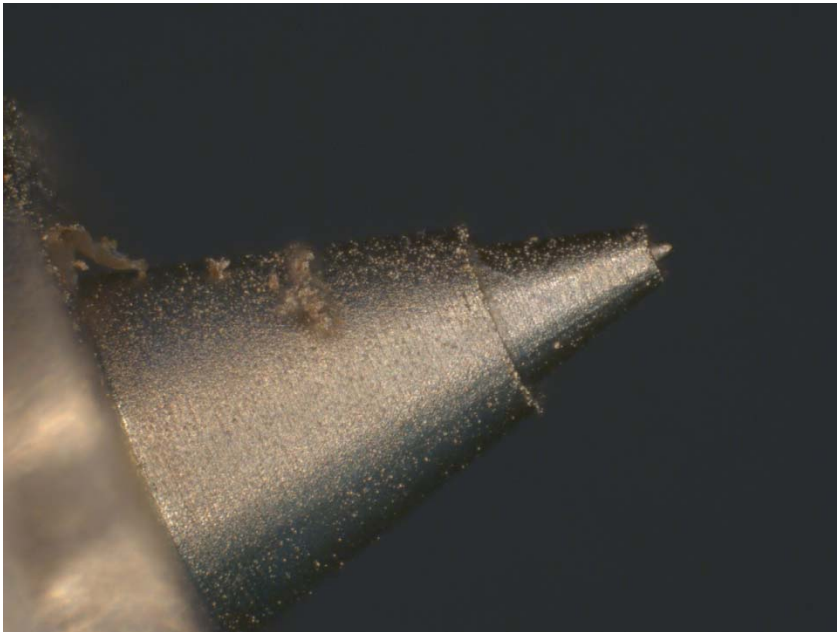
Copper Targets



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3 Metal Cone Slicing



Three metal layered cone
Required slicing to expose the
three layers.

Precision cutting using DPSS laser,
sliced layers of $\geq 5\mu\text{m}$ from the cone
until the three layers exposed.

Scitech 
PRECISION

Work performed with **Scitech Precision Ltd**



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Macro System

Variety of lenses from X30 – X1

Lens NA from 0.15 (X10)

Medium energy density

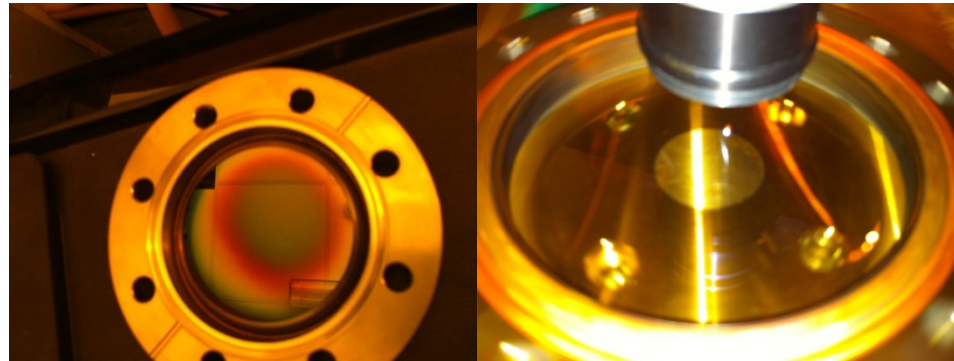
Suitable for materials such as diamond, sapphire, polymers, thin metal films
ceramics except fused silica, fluorides (MgF₂, BaF₂) and limits on metal layers
to ~100nm

Mask projection system allowing complex mask designs (lithography type
masks as well as our own metal masks)

Offset alignment using camera system

Limitations

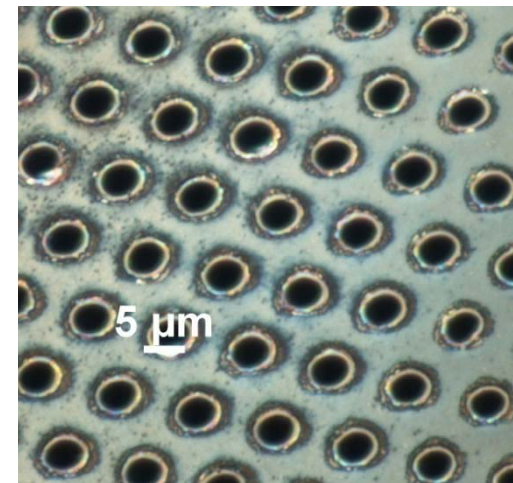
Exposure area. As large as 1:1 (10mm) for low fluence work but typically
2.5mm (X4) to 1mm (X10)





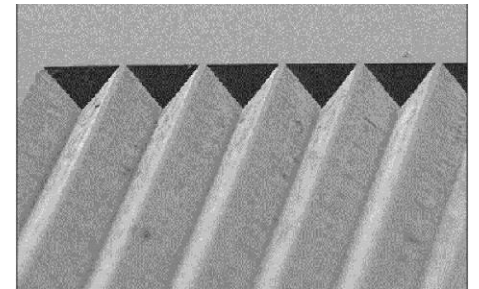
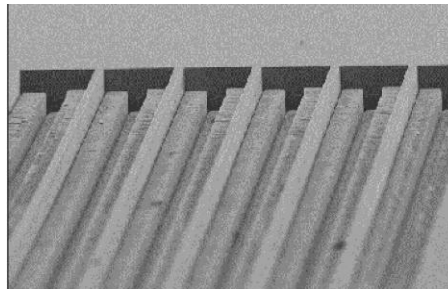
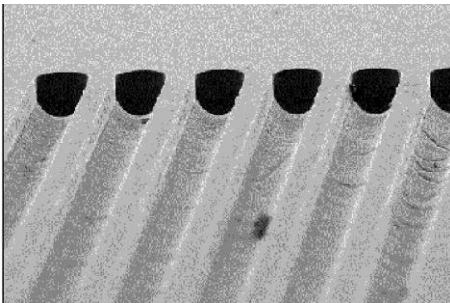
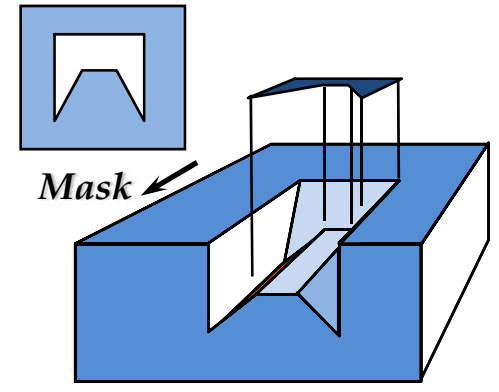
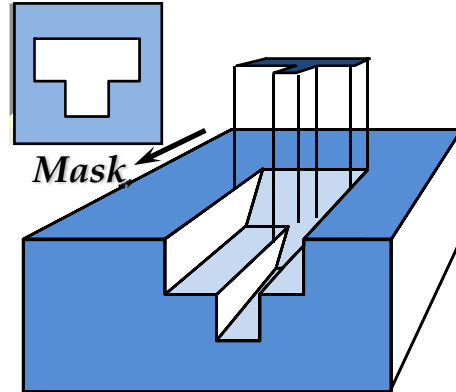
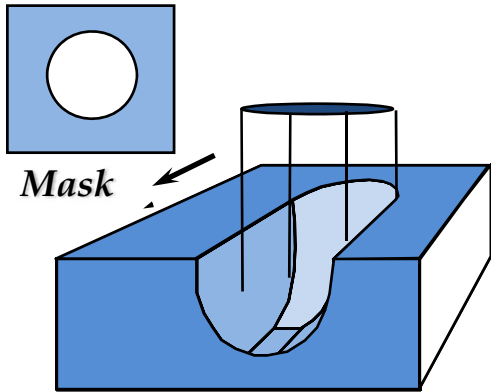
- 193nm Macro
 - Mask projection
 - Large area machining
 - Ideal for polymers, ceramics, diamond, sapphire
 - High resolution, micron level capability
 - Structured side walls, trenches.
 - Laser: Lambda Physik LPX220i

4um laser machined holes in sapphire



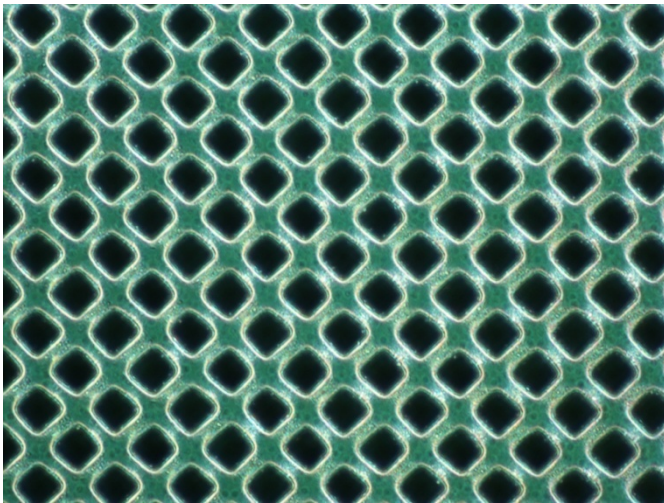


Mask Dragging: Profiles

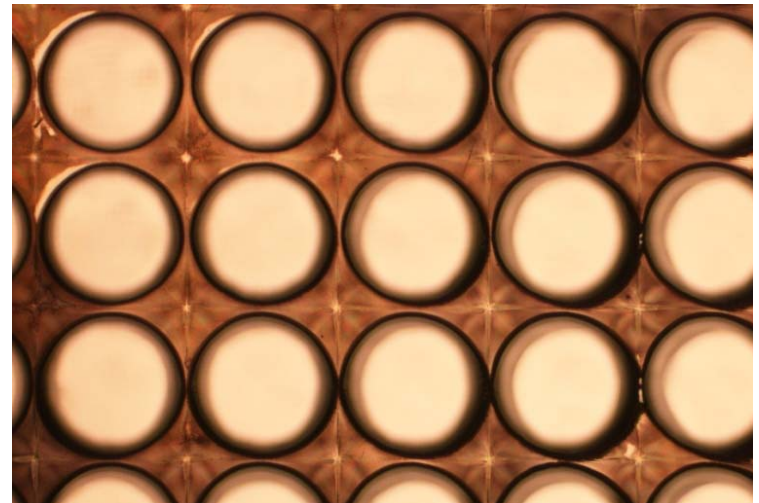




- A Mask can be complex, projecting thousands of features at the same time, similar to lithography.
- Direct machining



7um square holes machined in glass 1000's of holes /second

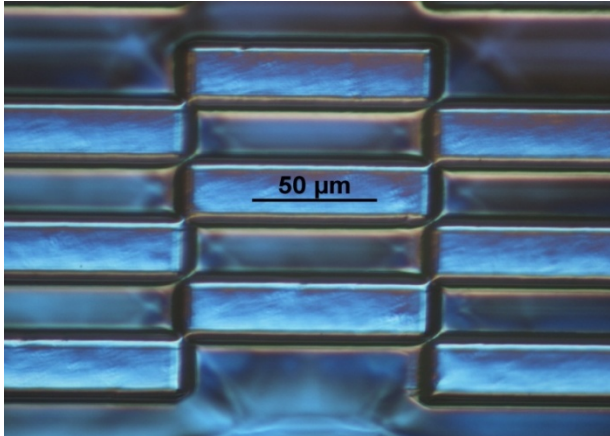


50um circular holes machined in polycarbonate

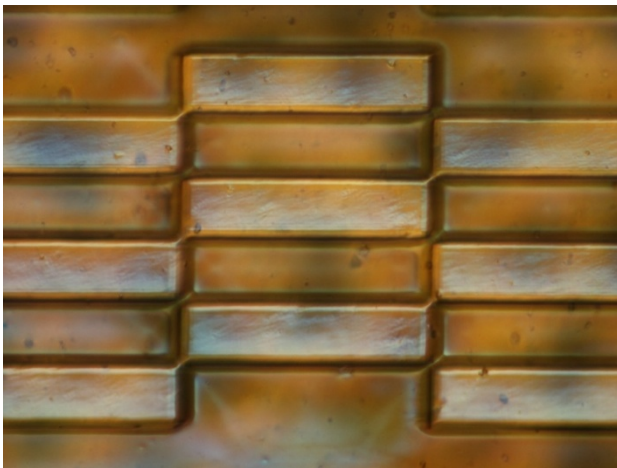


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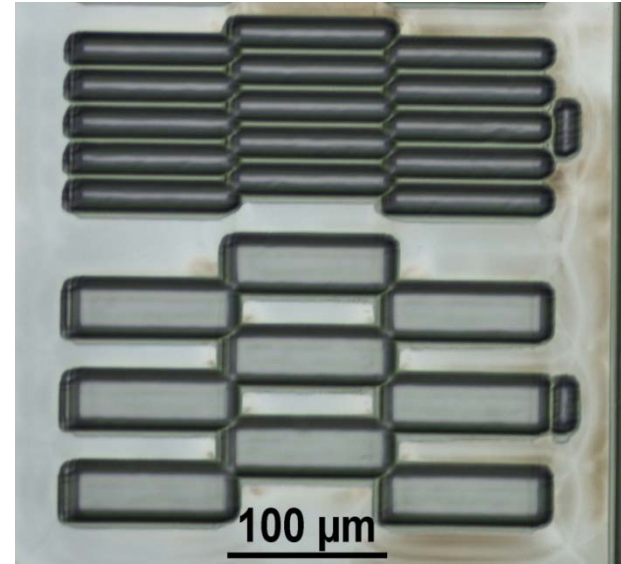
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Peek



Kapton

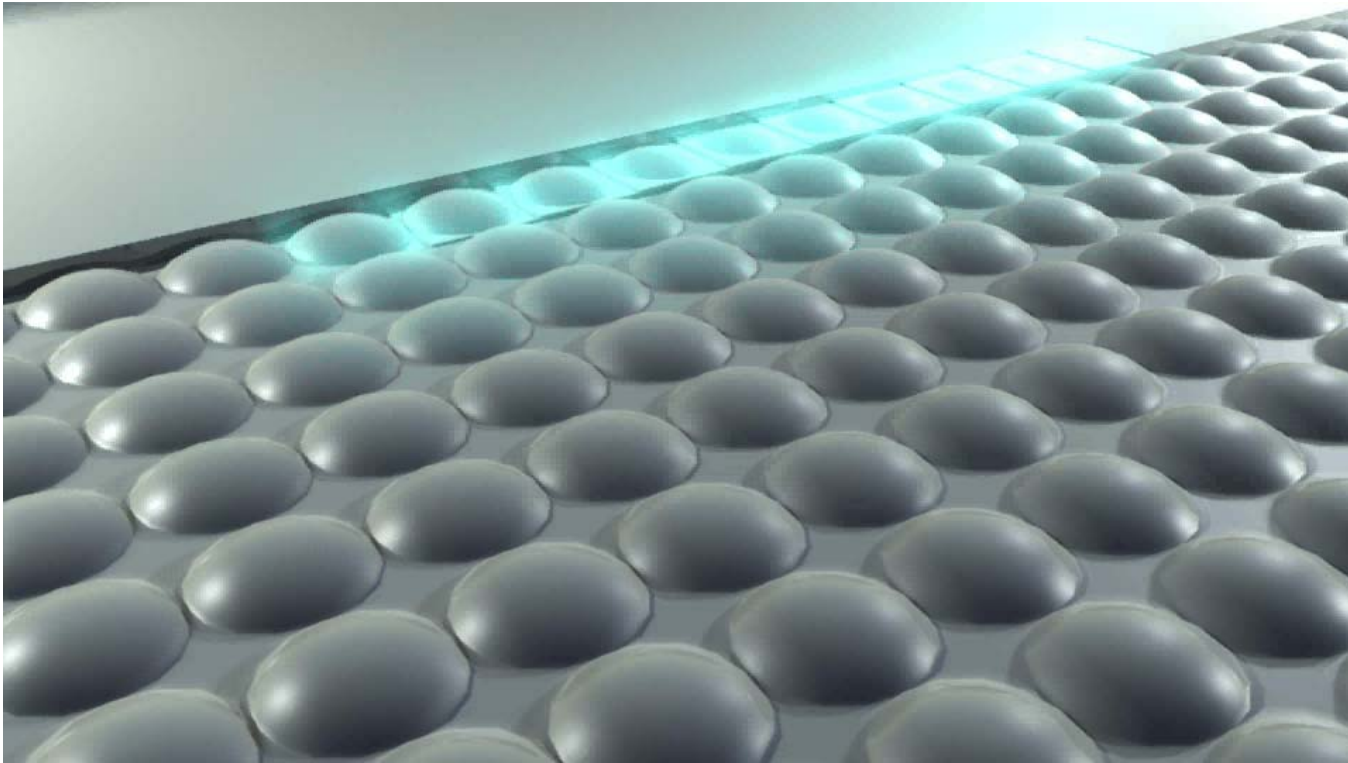


Polycarbonate

193nm Excimer



Sequential Image Scanning (SIS)





Micro System

Details

- 3 Magnifications, X15, X25 and X36
- High NA lenses, resolution approaching 0.5um
- High energy density
- Suitable for materials such as diamond, sapphire, polymers, thin metal films ceramics
- Not suitable for fused silica, DUV transmissive fluorides (MgF₂, BaF₂) limits on metal layers to less than 200nm
- Mask projection system allowing complex mask designs (lithography type masks as well as laser cut metal masks)
- Real-time alignment and observation using through lens camera system

Limitations

Exposure area. Mask area approx 10mm (X15= \sim 660 microns, X36= \sim 270um)



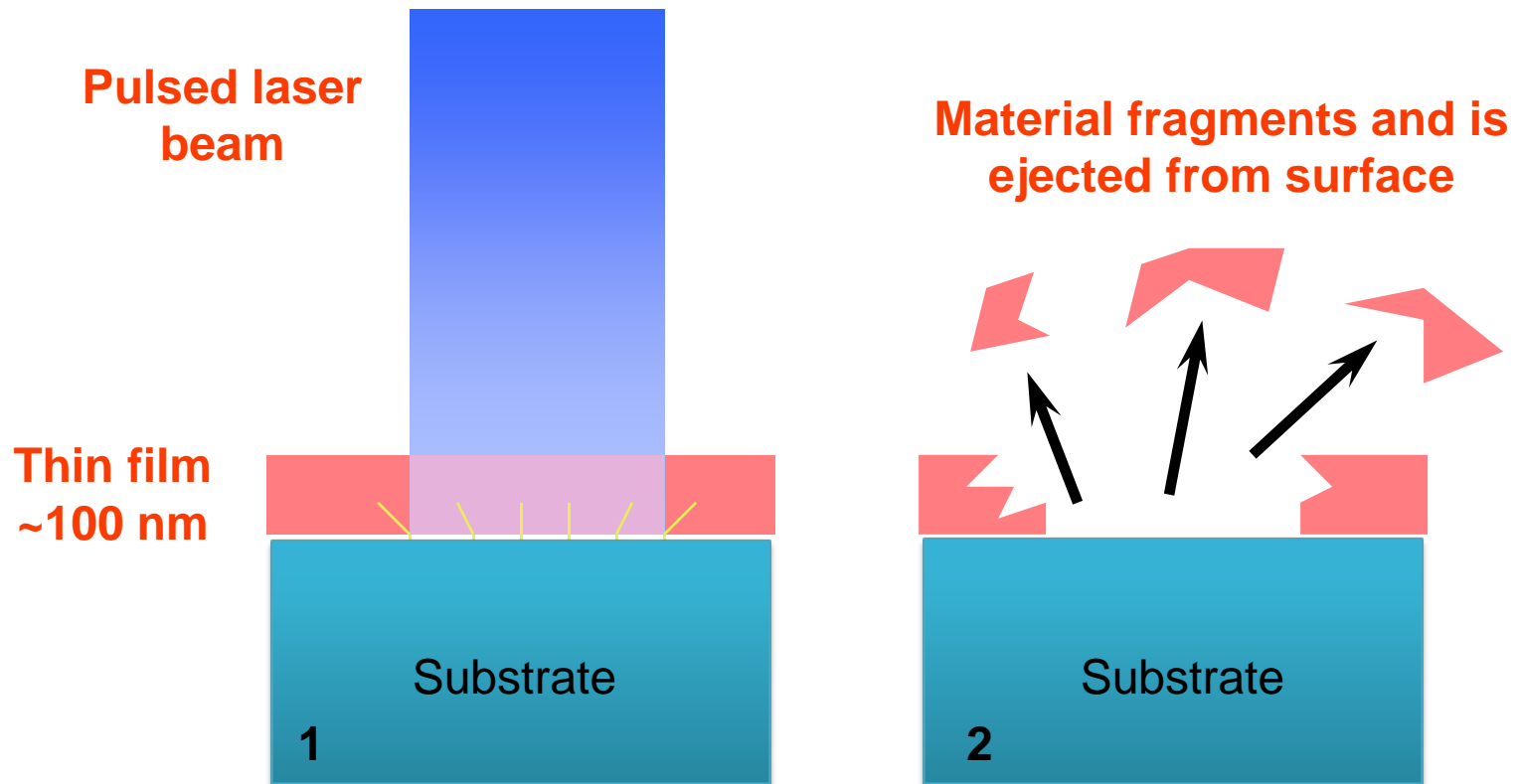
- 193nm Micro
 - Mask projection system capable of individual site machining or repair using direct backlit alignment
 - High NA lenses X15, X25 and X36 available
 - High Fluence $>20\text{J cm}^{-1}$
 - Lambda Physik Compex 205i
 - Areas up to 660um diameter



14um holes in Sapphire



Laser Interaction With Thin Films





Lift off Films



Aluminium 100nm
Laser cut metal masks
projected onto lift off film
1 Shot process

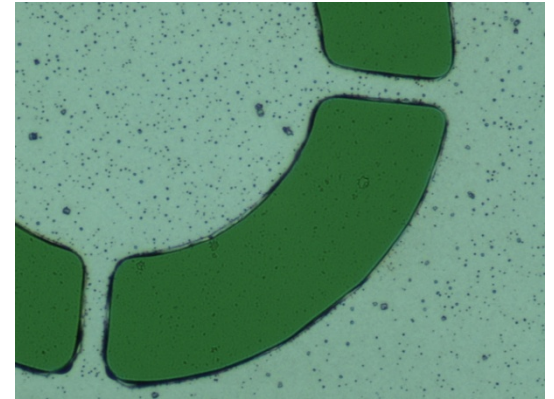
Fast delivery, from CAD to
patterned film can be less
than 12 Hrs

3 Step laser process.

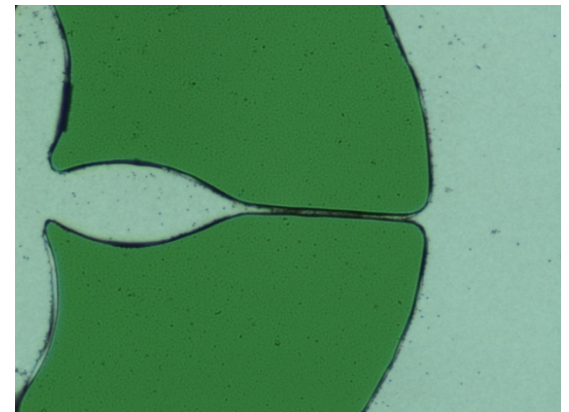
1. Mask
2. Projection
3. Profiling

Features to 2um achievable

Fast and Low cost process
compared to other
techniques



14um arm



2um arm



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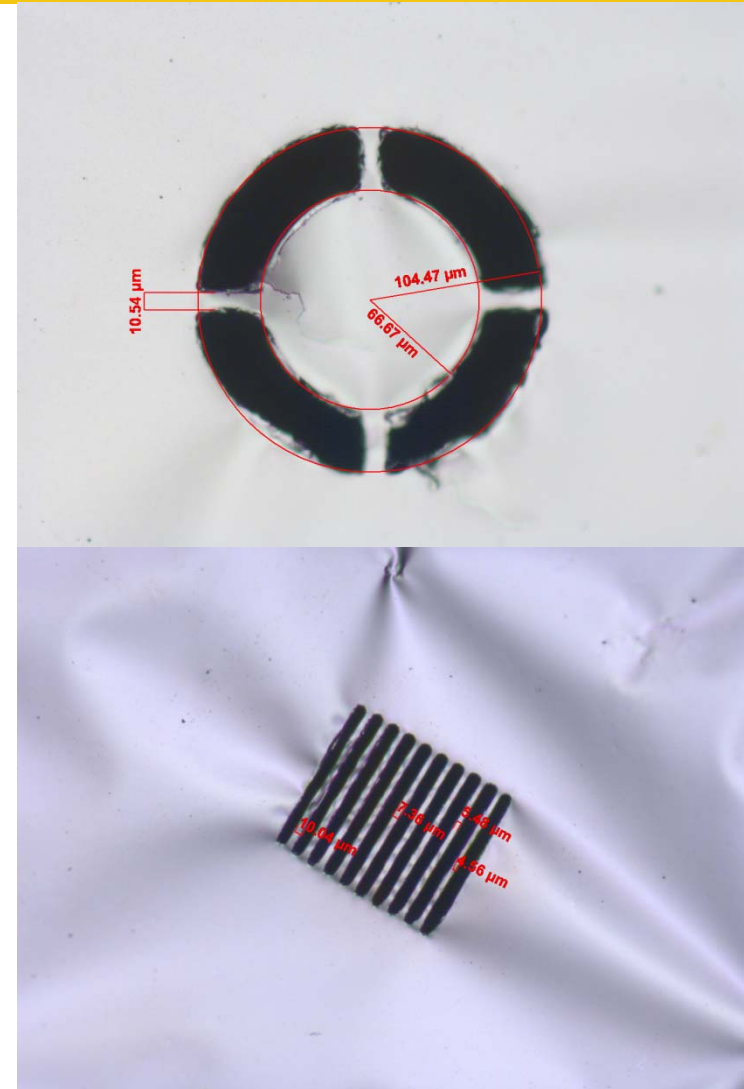
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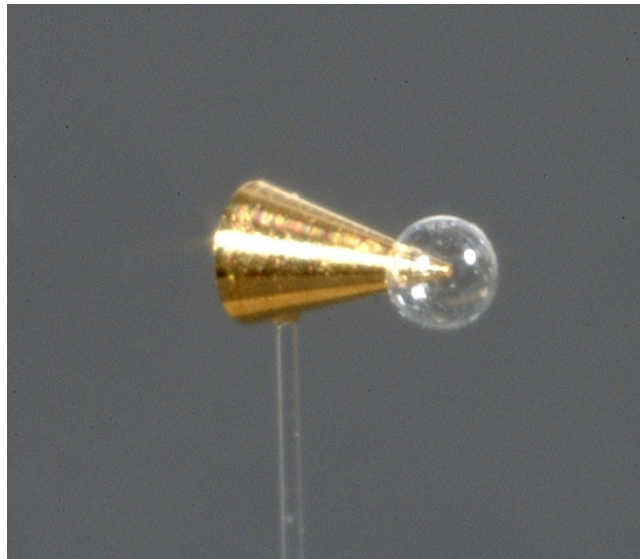
Lift off Film Targets 100nm Aluminium

Material:-100nm aluminium film

These targets have been successfully mounted,
features mounted so far extend down to 5µm

Lift off procedure and mounting performed by Scitech
Precision Ltd



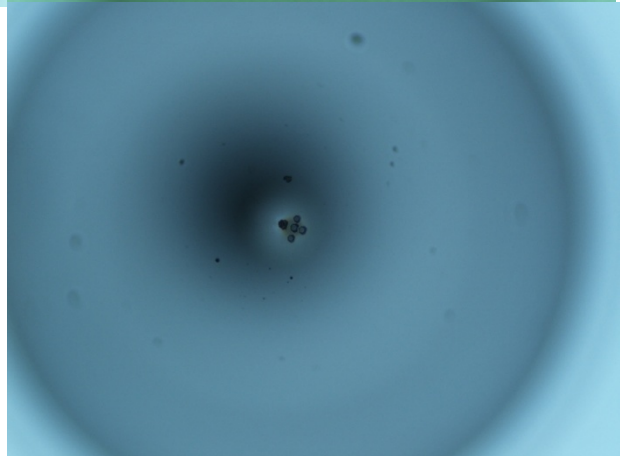
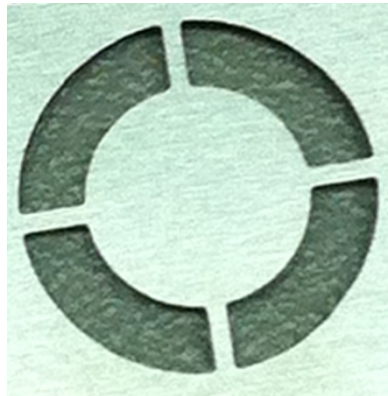
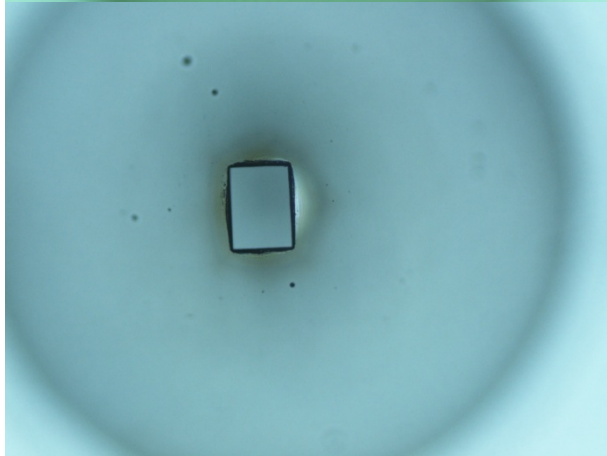
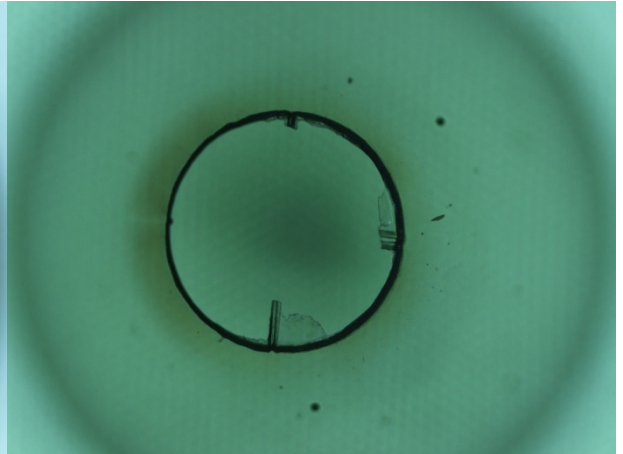
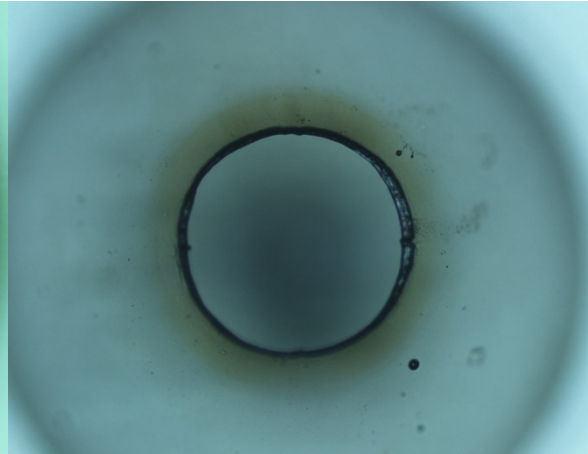
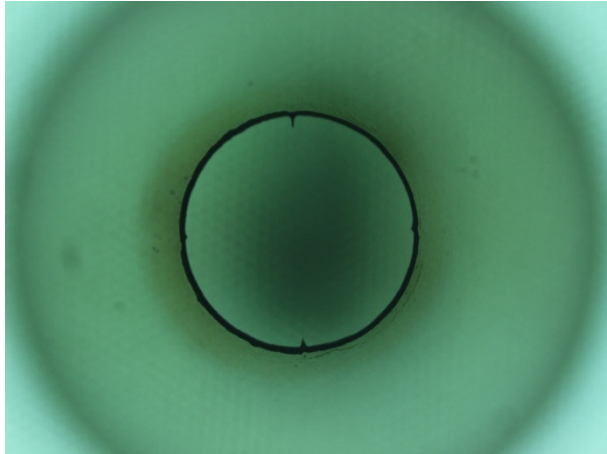


Sphere and Cone assembly Courtesy STFC



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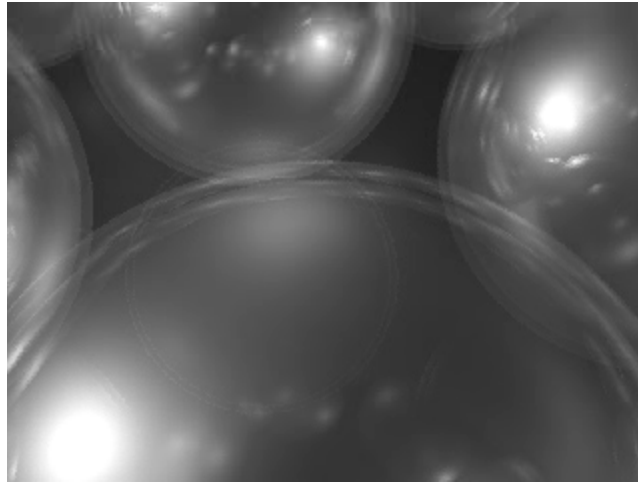


Metal mask example

5 x $\sim 10\mu$ holes



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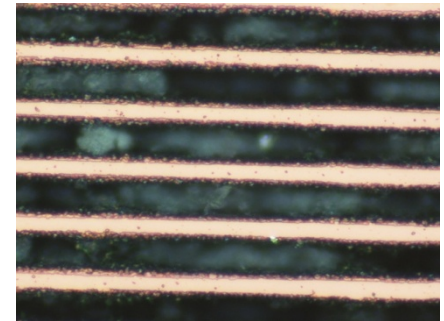
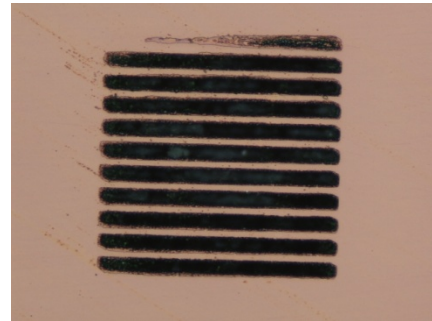
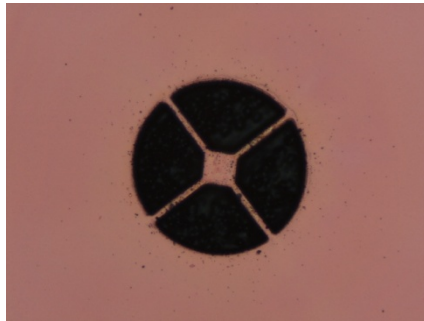
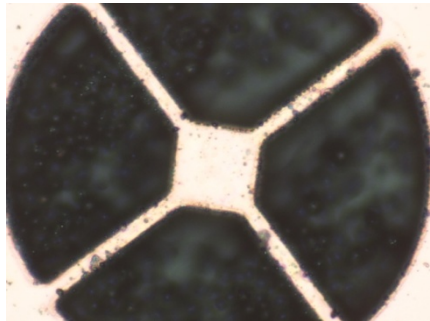




Dielectric Coated Laser Mirrors

Micro system machining of mirror coatings

- Sub 5μ resolution
- Dielectric coating intact

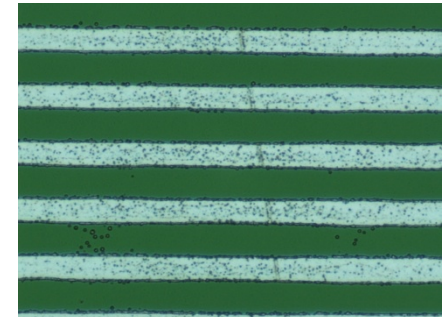
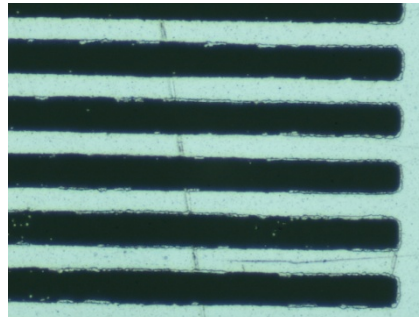
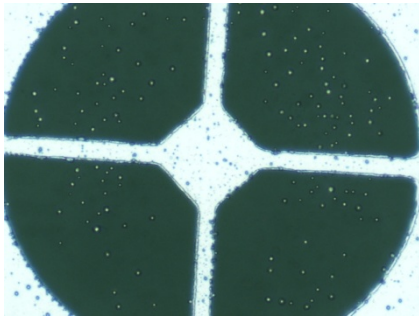




Aluminium Coated Laser Mirrors (MgF₂)

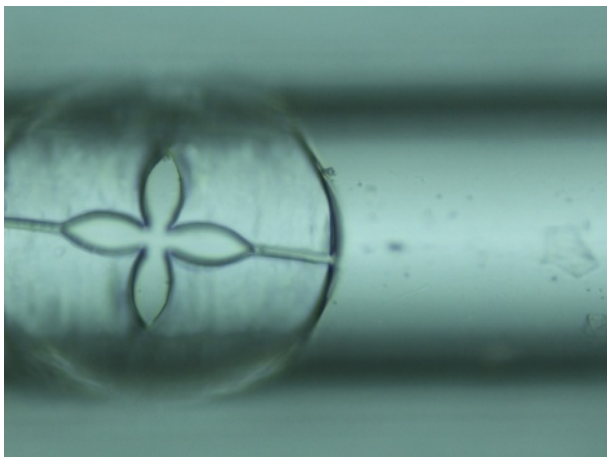
Micro system machining of Aluminium coatings

- Sub 5 μ resolution
- No damage to base material

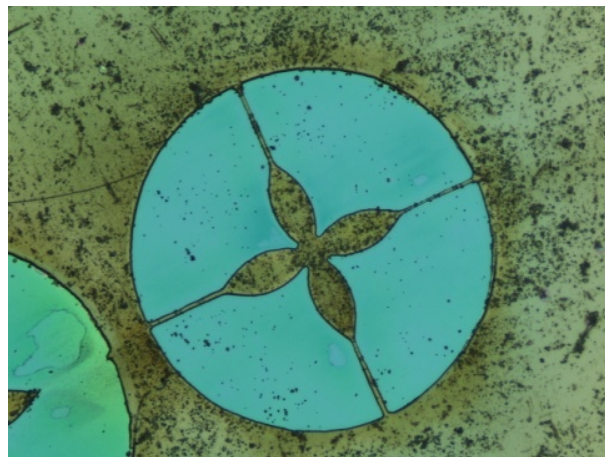




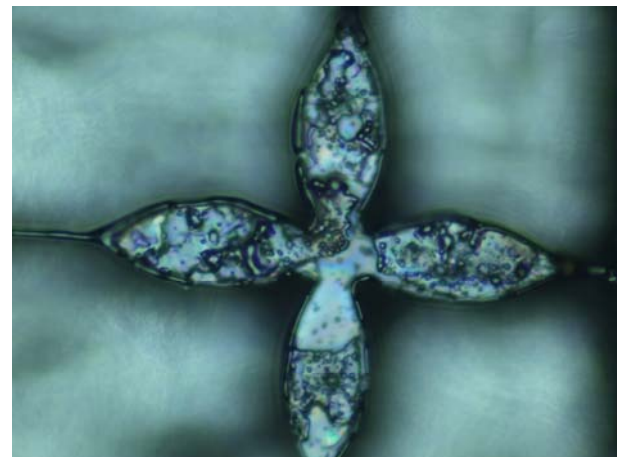
Other Materials



Fibre optics and
cladding



Kapton and most
polymers



CdWO₄



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Slot together targets?

Micronanics Limited offers a variety of services:

- Contact R&D
- Proof of Concept
- Micro-machining Services
- Production
- Laser Based Bespoke Solutions: Products and Machines
- Technical Animations
- Investigations into specialist material processing

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